

Electronic Supplementary Material

Two-photon lithography for 3D magnetic nanostructure fabrication

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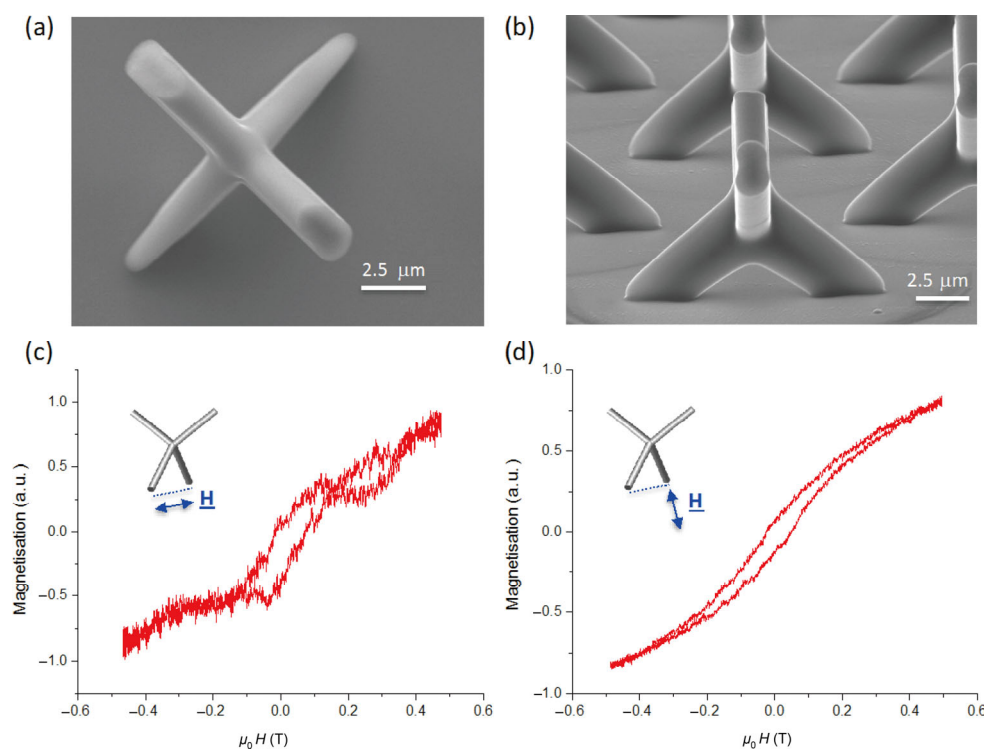


Figure S1 Tetrapod structures of larger feature size. (a) Scanning electron microscopy image of larger tetrapod structures (top view). (b) Scanning electron microscopy image of a larger tetrapod taken after 45° out-of-plane substrate rotation. Longitudinal MOKE loop of large tetrapod array with (c) field applied along projection of lower wires and (d) tetrapod array with field applied along projection of upper wires.

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